

L Number	Hits	Search Text	DB	Time stamp
1	107	"cleaning gas" and "deposition gas" and mixing	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:11
2	14	("cleaning gas" and "deposition gas" and mixing) and mixer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:09
3	10	"cleaning gas" near "deposition gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:14
4	4	"cleaning gas" near "deposition gas" and mix\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:36
5	12	"flow back prevention"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:36
6	0	"flow back prevention" and inert	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:36
7	479054	inert	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:36
8	34	inert and flowback	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:36
9	0	inert near flowback	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:36
10	0	flowback near inert	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:37
11	8	backflow near inert	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 13:18
12	3	"switching valve" near backflow	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 13:19
13	131	"cleaning gas" and mixer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 13:19
14	66	("cleaning gas" and mixer) and valve	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 13:20
-	395	700/ and "cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:48
-	86645	"chemical vapor deposition"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:48
-	896	"chemical vapor deposition" and "cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:48

	256	("chemical vapor deposition" and "cleaning gas") and @PD<20000101	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:49
	33	(("chemical vapor deposition" and "cleaning gas") and @PD<20000101) and "supply line"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:50
	29	"cleaning gas supply line"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:34
	2	"cleaning gas supply line" and "deposition gas" and flowing	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:55
	1	1995-094487	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 13:57
	529	"backflow gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:54
	5	"backflow gas" and prevent and "cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:35
	16	"backflow gas" and prevent and argon and helium	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:37
	1		USPAT	2004/01/13 15:37
	7	"6155289"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:37
	77	"backflow gas" and "flow rate" and ratio	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:54
	1	("backflow gas" and "flow rate" and ratio) and "cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:56
	6055	"cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 15:56
	9	"backflow gas" and "cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:08
	457	"carrier gas" and "cleaning gas"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:08
	105	("carrier gas" and "cleaning gas") and active and inert	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:12
	1	((("carrier gas" and "cleaning gas") and active and inert) and backflow	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:09
	91	("carrier gas" and "cleaning gas") and active and inert and argon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:12

-	62	("carrier gas" and "cleaning gas") and active and inert and helium	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:12
-	13	("carrier gas" and "cleaning gas") and active and inert and "argon helium"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/13 16:29
-	25	cleaning and "pre-coat" and semiconductor and gas	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/14 11:09